

Please replace the paragraph beginning on page 7, line 1, with the following rewritten paragraph:

*A2*  
--The substrate cleaned at the rinse module 62 is moved, via the transfer 74, into the strip module 64. The transfer 74 connects the rinse module 62 with the strip module 64 and includes a pipe shower 76 to prevent the substrate from drying. The strip module 64 strips the photoresist on the substrate using a stripper liquid.--

IN THE CLAIMS:

Please amend the claims as follows:

*A3*  
1. (As Amended) An etch/strip apparatus integrated with cleaning equipment, comprising:  
an etching line for etching and cleaning a substrate;  
a stripping line for stripping the substrate, the stripping line being connected to the etching line; and  
a cleaning line installed on the stripping line to clean and dry the substrate, wherein the etch/strip apparatus is a single piece of equipment.

*A4*  
3. (As Amended) The apparatus as claimed in claim 1, further comprising:

a transfer for moving the substrate from the etching line to the stripping line, the transfer being between the etching line and the stripping line.

4. (As Amended) The apparatus as claimed in claim 1, further comprising:

a loader for feeding the substrate to the etching line; and an unloader for receiving the substrate from the cleaning line.

5. (As Amended) The apparatus as claimed in claim 4, wherein the etching line includes:

an etch module for etching the substrate from the loader; and

a rinse module for cleaning the substrate fed from the etch module.

6. (As Amended) An integrated etch/strip/clean apparatus,

comprising:

an etching line for etching and cleaning a substrate;  
a stripping line for stripping said substrate; and  
a cleaning line integrated with said etching and stripping lines to clean and dry the substrate, wherein the etch/strip/clean apparatus is a single piece of equipment.

12. (As Amended) The apparatus of claim 6, further comprising:  
AS  
a loader for loading the substrate to the etching line; and  
an unloader for unloading the substrate from the cleaning  
line.

Please add the following claims:

--15. The apparatus as claimed in claim 1, wherein the  
stripping line and the cleaning line are stacked to have a two-  
tier structure.--

AB  
AS  
--16. The apparatus as claimed in claim 6, wherein the  
stripping line and the cleaning line are stacked to have a two-  
tier structure.--

Attached hereto is a marked-up version of the changes made to  
the application by this Amendment.